CH5. 攜散

Intro

擴散現象可擴散偶描述,原子互換擴散的過程→interdiffusion,也可以稱 impurity diffusion

純金屬中的擴散→self-diffusion→無法由成分改變觀察→By radioactive isotopes

Kirkendall effect

二元擴散偶的介面標示物,朝著和"較快擴散速度物種"相反的方向移動→因為 vacancy 的存在

機構

原子觀點,擴散是原子在 lattice site 之間的 stepwise migration,實際上,原子 are in constant motion,並快速的變換位置

想移動,必須

- 1.旁邊有空位
- 2.能量足夠去斷鍵→振動(活化能夠)
- 一般熔點越高的金屬→鍵結較強→活化能就越高

對金屬擴散而言,兩種最常用的 model,

Vacancy Diffusion(substitutional diffusion)

- 1.為缺陷(vacancy)數目的函數(與溫度有關,T越大越多 vacancy)
- 2.相當於 vacancy 往反方向移動
- 3. self-diffusion 是藉由這種機構

Interstitial Diffusion

C.H.O.N 等小原子屬於 interdiffusion(impurity),且 interstitial atom 比 vacancy 小,interstitial position 又比較多→ Interstitial Diffusion 機率大於 Vacancy Diffusion

- *再強調一次,自擴散是藉由空位機構,C在鐵中擴散是 interstitial
- *interdiffusion 二種機構都可能

定義

diffusion flux

$$J = \frac{M}{At}$$

如果 J 不隨時間改變→ steady-state diffusion

Fick's first law 驅動力是濃度梯度,實際應用→ 氫氣純化(注意各 unit)

$$J = -D\frac{dC}{dx} \quad \text{or in SI unit form, } \left\{ \frac{\text{atoms}}{\text{m}^2 \cdot \text{s}} \right\} = \left\{ \left(\frac{\text{m}^2}{\text{s}} \right) \left(\frac{\text{atoms}}{\text{m}^3} \times \frac{1}{\text{m}} \right) \right\}$$

where J =flux or net flow of atoms;

D = proportionality constant called the diffusivity (atomic conductivity) or diffusion coefficient;

$$\frac{dC}{dx}$$
 = concentration gradient.

Fick's second law

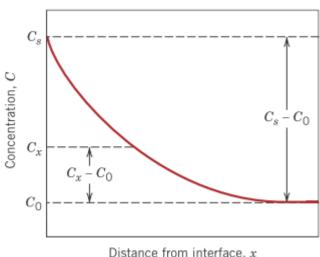
$$\frac{dC_x}{dt} = \frac{d}{dx} \left(D \frac{dC_x}{dx} \right)$$

$$\frac{\partial C}{\partial t} = D \frac{\partial^2 C}{\partial x^2}$$

*假設了 D 與成分無關

$$\frac{C_x - C_0}{C_s - C_0} = 1 - \operatorname{erf}\left(\frac{x}{2\sqrt{Dt}}\right)_{---(1)}$$

注意等式兩邊都是無因次



Distance from interface, x

擴散係數 D 是擴散速率的指標,

擴散物種和 host material 都會影響,亦會受溫度影響

*注意擴散係數 D 之單位為 (m²/s) 會考!可以由使此式無因次來推論

$$D = D_0 \exp\left(-\frac{Q_d}{RT}\right)_{--(2)}$$
 erf $\left(\frac{x}{2\sqrt{Dt}}\right)$

"short-circuit" diffusion paths

延著差排.晶界.外表面的原子遷移較快,但整體貢獻不明顯,因為這些路徑截面 積小

5.44 Is the non-steady diffusion process more sensitive to temperature or time? Explain using appropriate equations.

由上面(1)式, D和t的影響是一樣的,然而由(2)式可之小小的溫度T改變,可引 發很大的 D 變化,所以溫度和時間相比,擴散對於溫度是比較敏感的。 (直覺也該是溫度)

(a) The solution to Fick's second law for a diffusion couple composed of two semi-infinite solids of the same material is as follows:

$$C_x = \left(\frac{C_1 + C_2}{2}\right) - \left(\frac{C_1 - C_2}{2}\right) erf\left(\frac{x}{2\sqrt{Dt}}\right)$$

Smith 補充

二種擴散製程

藉氣體碳化而硬化鋼(滲碳)

先退火狀態對鋼件加工→再表面硬化(滲碳)

滲碳→鋼件置入 furnace 中(約 927°C),與 CH₄ 或其它碳氫化合物(rich in CO)接觸→產生 <u>hard outer later & tough low carbon steel inner core</u> 的 <u>duplex structure</u> 滲碳鋼為低碳鋼!通常只有 0.1%~0.25%的碳

矽晶圓的雜質擴散

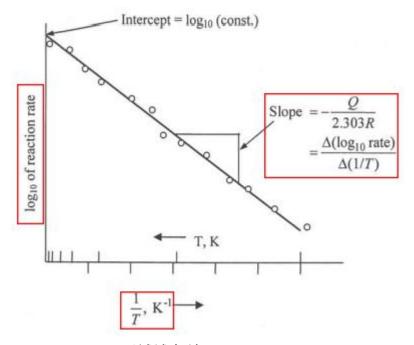
目的:雜質滲入改良導電性質

在 1100°C 的石英管爐,使矽晶圓暴露在雜質蒸汽,透過遮蔽使雜質滲入指定位置。

一般系晶元的擴散深度在數個微米等級(10⁻⁶m),晶圓厚度約為數百個微米

Arrhenius 方程式

→typical Arrhenius plot



Kirkendall effect:已補述在前

5.40 The self-diffusion of iron atoms in BCC iron is significantly higher than in FCC iron (See Table 5.2). Explain why.

因為 BCC 的 APF 較低

5.41 The melt temperatures of copper and aluminum are 1083°C and 657°C respectively. Compare the diffusivities of copper in copper and copper in aluminum at 500°C (use Table 5.2). Can you explain why a drastic difference exists?

因為銅的熔點較高,鍵結比較強,較難擴散

第二個原因是銅半徑較小,又兩者皆 FCC,所以銅的 void spaces 較小

5.42 Would you expect the diffusion rate of copper (self diffusion) to be lower or higher in copper with ASTM grain size 4 than in copper with ASTM grain size 8?
Explain your answer.

ASTM 號碼越高→越 fine→越多晶粒和晶界

注意到晶界較鬆散,擴散較快!

所以號碼越高→會有較高的自擴散

5.43 Would you expect the diffusion rate of copper (self-diffusion) to be lower in a pure copper sample that is loaded with dislocations or in a pure copper sample that is free of dislocations (refer to Sec. 4.4.2 for characteristics of dislocations)? Explain your answer.

有差排會有更高的儲存能,原子的較高能態會幫助擴散過程。

5.45 In NaCl, would you expect the activation energy of cation (Na⁺) to be higher or the anion (Cl⁻)? Why?

陽離子比較小,較易擴散,所以活化能較小